



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Kyoichi SUWA

Application No.: 09/729,339

Filed: December 5, 2000

Docket No.: 108057

For: MASK, EXPOSURE METHOD, LINE WIDTH MEASURING METHOD, AND METHOD  
FOR MANUFACTURING SEMICONDUCTOR DEVICES

INFORMATION DISCLOSURE STATEMENT

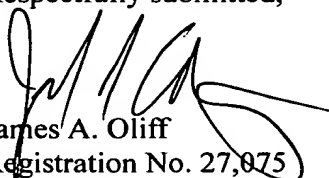
Director of the U.S. Patent and Trademark Office  
Washington, D.C. 20231

Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the reference(s) listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- ☒ 1. This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of a first Office Action on the merits in the present application. No certification or fee is required.
- ☒ 2. Partial translations of the non-English language references are attached.

Respectfully submitted,

  
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JAO:JSA/zmc

Date: April 20, 2001

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